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Jul 3, 2001

DERWENT-ACC-NO: 2002-245504
DERWENT-WEEK: 200230
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$Al_2O_3 + Y_2O_3$
substrate

TITLE: Ceramic member for apparatus e.g bell jar used in semiconductor manufacturing apparatus, comprises oxide containing preset weight percent of yttrium oxide in portions exposed to halogen gas or halogen gas plasma.

PATENT-ASSIGNEE:

ASSIGNEE

NIPPON CERATEC CO LTD

TAIHEIYO CEMENT CORP

CODE

NICEN

ONOD

PRIORITY-DATA: 1999JP-0368828 (December 27, 1999)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
JP 2001181024 A	July 3, 2001		004	C04B035/44

APPLICATION-DATA:

PUB-NO	APPL-DATE	APPL-NO	DESCRIPTOR
JP2001181024A	December 27, 1999	1999JP-0368828	

INT-CL (IPC): B01 J 19/02; C04 B 35/00; C04 B 35/44; C04 B 35/50

ABSTRACTED-PUB-NO: JP2001181024A

BASIC-ABSTRACT:

NOVELTY - The portion of ceramic member which is exposed to halogen gas or halogen gas plasma, consists of oxide containing complex oxide, aluminum oxide and 30 weight% or more of yttrium oxide. The porosity of ceramic member is 3-8%.

USE - For apparatus such as bell jar, chamber, susceptor, clamp ring, and focal ring used in semiconductor manufacturing apparatus.

ADVANTAGE - The ceramic member has high resistance to halogen gas or halogen gas plasma, and high heat resistance property.

CHOSEN-DRAWING: Dwg.0/0

TITLE-TERMS: CERAMIC MEMBER APPARATUS BELL JAR SEMICONDUCTOR MANUFACTURE APPARATUS COMPRISE OXIDE CONTAIN PRESET WEIGHT YTTRIUM OXIDE PORTION EXPOSE HALOGEN GAS HALOGEN GAS PLASMA

DERWENT-CLASS: L02 L03 U11

CPI-CODES: L02-G; L04-D;

EPI-CODES: U11-C09X;

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: C2002-073736